

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
Eugene P. Marsh

Serial No.: 10/634,362

Filed: August 8, 2003

For: **ATOMIC LAYER DEPOSITION OF
METAL DURING THE FORMATION
OF A SEMICONDUCTOR DEVICE**



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Group Art Unit: 2812

Examiner: Lynne Ann Gurley

Atty. Docket: 2003-0659.00/US

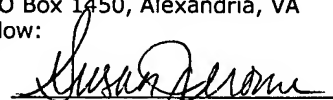
Confirmation No. 4954

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Certificate of Mailing (37 CFR §1.8)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to:
Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on the date below:

May 20, 2004
Date


Signature

INFORMATION DISCLOSURE STATEMENT

In compliance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant respectfully requests that this Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. A copy of the listed reference is enclosed.

In accordance with 37 C.F.R. § 1.97(g), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 C.F.R. § 1.56(a) exists.

The following reference is submitted for the Examiner's review:

"Cobalt Metallorganic Chemical Vapor Deposition and Formation of Epitaxial CoSi₂ on Si(100) Substrate," Hwa Sung Rhee et al., Journal of the Electrochemical Society, 1999, pp. 2720-2724.

05/25/2004 HTECKLU1 00000068 133092 10634362

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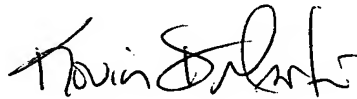
This Information Disclosure Statement is being submitted after the mailing of the first Office Action, but before the mailing of a Final Rejection or Notice of Allowance. The Commissioner is authorized to charge the fee set forth in 37 C.F.R § 1.17(p) of \$180 and any additional fees which may be required to Micron Technology Inc. Deposit Account No.13-3092, Order No. 2003-0659.00/US.

If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicant's undersigned agent at the number indicated.

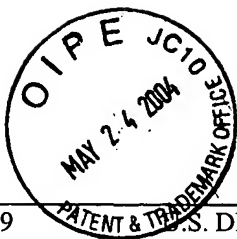
* * * *

Form PTO-1449 is enclosed herewith.

Respectfully submitted,



Kevin D. Martin
Reg. No. 37,882
Micron Technology, Inc.
8000 S. Federal Way
Boise, ID 83706-9632
(208) 368-4516
Agent for Applicant



Sheet: 1 of: 1

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|--|--|------------------------------------|--------------------------|
| FORM: PTO-1449 (REV: 7-80) | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | Atty Docket No: 2003-0659.00/US | Serial No: 10/634,362 |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b)) (use several sheets if necessary) | | Applicant: Eugene P. Marsh | |
| | | Filing Date: August 8, 2003 | Group: 2812 |

U.S. PATENT DOCUMENTS

| Examiner Initial | Document Number | Date | Name | Class | Subclass | |
|---------------------|--------------------|------|------|-------|----------|--|
| | AA | | | | | |
| | AB | | | | | |
| | AC | | | | | |
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FOREIGN PATENT DOCUMENTS

| Examiner Initial | Document Number | Date | Country | Class | Subclass | Translation | |
|---------------------|--------------------|------|---------|-------|----------|--------------------------|--------------------------|
| | AO | | | | | Yes | No |
| | AP | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| | AQ | | | | | <input type="checkbox"/> | <input type="checkbox"/> |

| Initial | OTHER ART (including author, title, date, pertinent pages, etc.) | | |
|---------|---|--|--|
| | AR | | "Cobalt Metallorganic Chemical Vapor Deposition and Formation of Epitaxial CoSi ₂ Layer on Si(100) Substrate", Hwa Sung Rhee et al, Journal of The Electrochemical Society, 1999, pp. 2720-2724 |
| | AS | | |
| | AT | | |

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| Examiner: | Date Considered: |
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.